



(51) International Patent Classification:
C09D 133/14 (2006.01) *G03F 7/039* (2006.01)

(21) International Application Number:
PCT/IB2009/005975

(22) International Filing Date:
17 June 2009 (17.06.2009)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
12/141,307 18 June 2008 (18.06.2008) US

(71) Applicant (for all designated States except US): **AZ ELECTRONIC MATERIALS USA CORP.** [US/US];
70 Meister Avenue, Somerville, NJ 08876 (US).

(72) Inventors: **THIYAGARAJAN, Muthiah**; 4504 Patterson Street, Bridgewater, New Jersey 08807 (US). **CAO, Yi**; 8 Willow Court, Clinton New Jersey 08809 (US). **HONG, Sung Eun**; 70 Patriot Hill Drive, Basking Ridge, New Jersey 07920 (US). **DAMMEL, Ralph R.**; 8 Quimby Lane, Flemington, New Jersey 08822 (US).

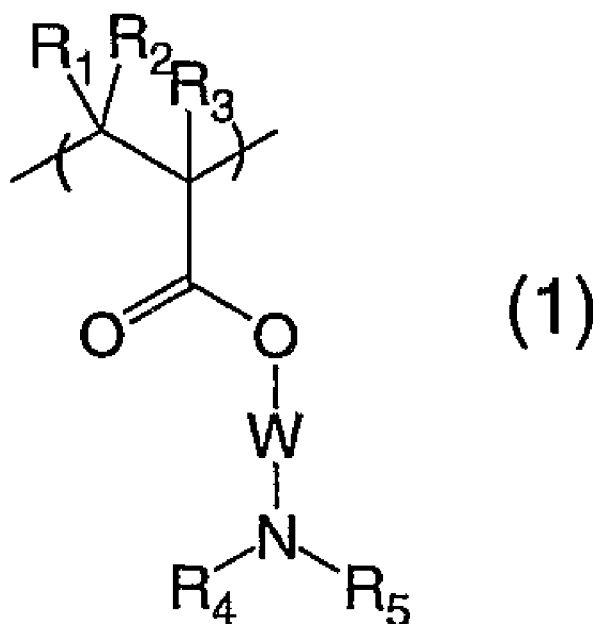
(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

— with international search report (Art. 21(3))

(54) Title: AQUEOUS COMPOSITION FOR COATING OVER A PHOTORESIST PATTERN



(57) Abstract: The present invention relates to an aqueous coating composition for coating a photoresist pattern, comprising a polymer comprising at least one unit with an alkylamino group, where the unit has a structure (1), where, R_1 to R_5 are independently selected from hydrogen and C_1 to C_6 alkyl, and W is C_1 to C_6 alkyl. The invention also relates to a process for imaging a photoresist layer using the present composition.